



Introduction to Pixelligent Technologies

2024 Phabulous Micro-Optics Summit & Expo, Dec 2, 2024

Alex Everett– Account Manager

Pixelligent at a Glance

Pixelligent is a leading manufacturer of market-leading nanocomposites for multiple fast-growing applications

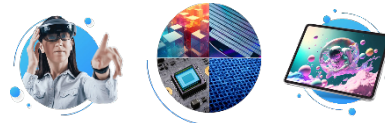
What We Do

- We synthesize and cap small metal-oxide nanocrystals
- We make custom formulations for various applications



Why We Do it

- To create unparalleled optical properties that enable superior light management in devices



How We Do it

- Award-winning development & manufacturing platform
- Leverage AI to accelerate product development

Who We Do it for

- Leading consumer electronics companies across the globe

What Are Our Core Markets

Extended Reality ("XR"): AR / MR



- **PixNIL®** enables the widest field of view in XR devices
- Refractive Index 1.7 - 2.0
- Solvent containing
- Nanoimprint Lithography (NIL)

Optics / Sensors



- **PixClear®** improves light capture & focusing power on sensors & optics
- Refractive Index 1.65 - 1.9
- Solvent-free formulations
- Microimprintable

Displays



- **PixJet®** significantly increases brightness in displays & extends battery life
- SFZ5 is designed for OLED outcoupling

Award Winning Manufacturing

Scalable, High Yield, Efficient and High-Quality Manufacturing

- **In-Place High Volume Capacity:** Current manufacturing facility provides foundation to support near-term demand and growth.
- **Raw Materials:** Readily available from multiple global sources.
- **Equipment:** Standard equipment and processes in custom configurations. Equipment parts are available from multiple suppliers.
- **Process:** Uses standard proven wet chemistry processes.
- **Technology:** Proprietary, scalable, repeatable and robust.
- **Environmental Compliance:** Fully TSCA and REACH compliant in all required countries.
- **Quality Management:** ISO9001 Certified.
- **Award Winning:** Named Manufacturer of the Year by Frost & Sullivan in 2017.

Facilities Overview

Location:	Headquarters, Manufacturing Facility in Baltimore, MD.
Square Feet:	18,000 square feet of chemical manufacturing and lab space.
Current Capacity:	• PixClear® Zirconia: 10 metric tons / year • PixClear® Titania: 15 metric tons / year • PixClear® Formulations: 20 metric tons / year
Standby Capacity:	80 metric tons of PixClear® Zirconia/Titania

10 Ton Synthesis Reactor



Capping Reactor



80 Ton Synthesis Reactor



Pixelligent Evolution

Pixelligent 1.0

Develop and scale synthesis & capping of NPs < 20nm at multi-ton scale

Pixelligent 2.0

Extend the PixClearProcess® to 3 metal oxide platforms, PixClear HfO₂, ZrO₂, and TiO₂

Pixelligent 3.0

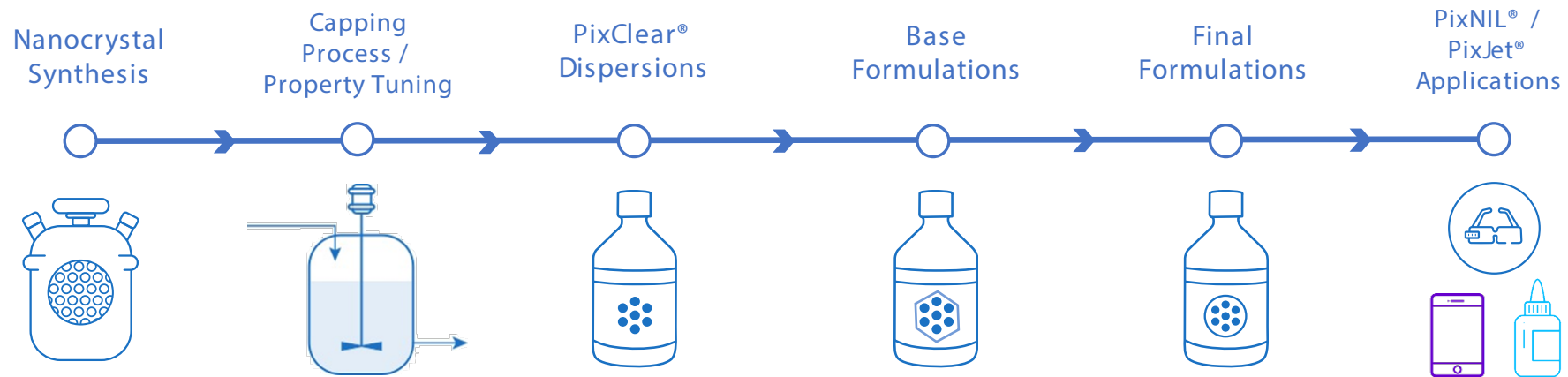
Introduce formulated products for the display, XR, and Optics markets – PixJet®, PixNIL®, PixCor™

Pixelligent 4.0

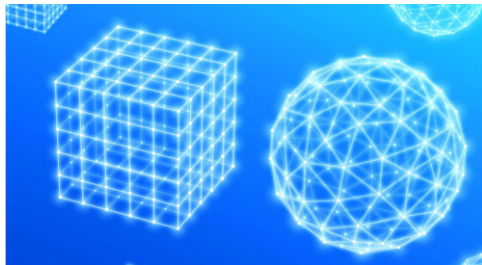
Implementing AI platform to accelerate introduction of 15-20 new PixClear® metal oxides across Display, XR, Optics, Semiconductor, and Energy storage markets.

The PixClearProcess®

The Proprietary PixClearProcess® Development and Manufacturing Platform



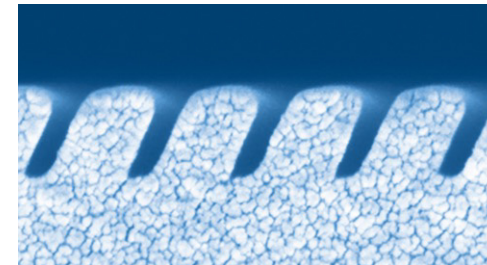
NANOCRYSTALS



DISPERSIONS



PIXNIL APPLICATION



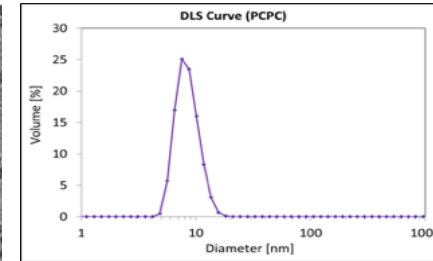
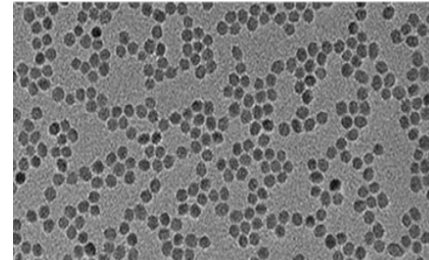
25 Additional Metal Oxide materials in the Pipeline that will leverage the PixClearProcess® Platform → Barium Titanate next.

Highest Quality Nanocrystals

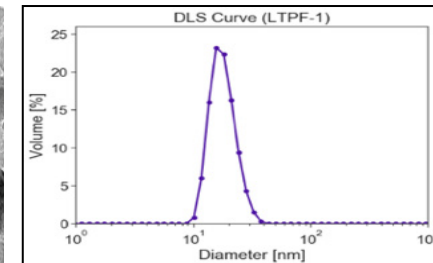
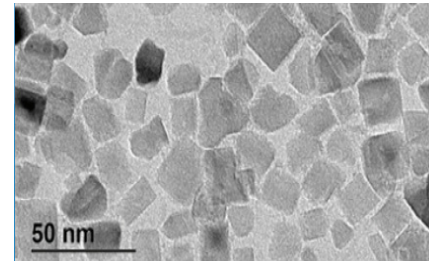


The PixClearProcess® is a proprietary synthesis and capping process for uniform and controlled particle sizes:

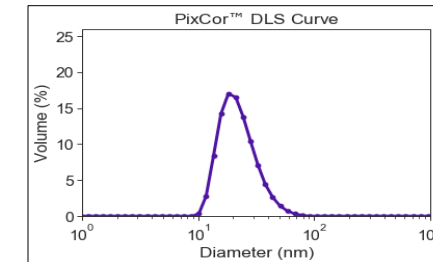
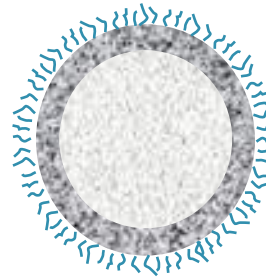
- ✓ Core Particle size to 3nm – 15nm; 5nm -20nm capped (TEM)
- ✓ Film RI: 1.7 – 2.0+ at 589 nm
- ✓ > 95%+ transparencies in the visible light range
- ✓ Organic/Inorganic capping agents; polar/non-polar solvents (move to capping agent slide)
- ✓ Monodisperse with 99.99% of particle diameter < 30nm for ZrO₂ and < 70 nm for TiO₂ dispersions



*Zirconia
(10 nm)*



*Large Titania
(20 nm)*



*PixCor™
(20 nm)*

Nanocrystal Surface Modification



Capping agents

- Improve dispersibility
- Enables compatibility
- Reduces surface effects

Long capping agent

- Low/loose packed surface coverage

Short capping agent

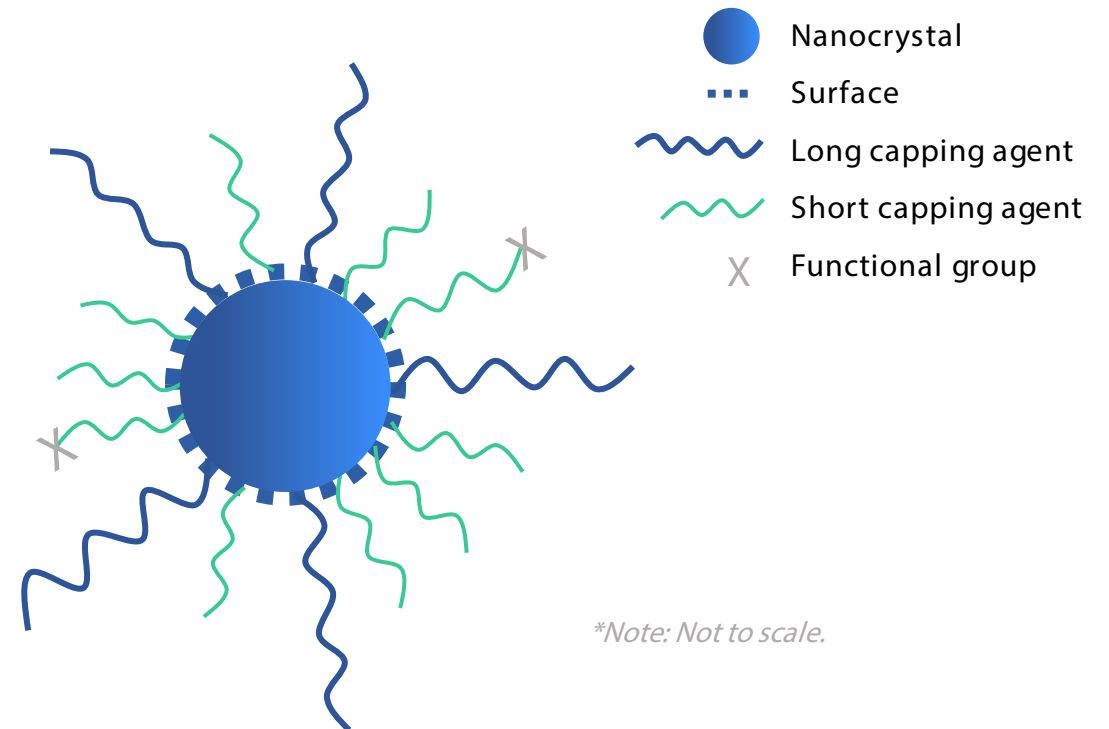
- High/dense packed surface coverage

Functional capping agents

- Crosslink into polymer
- Acrylates and others

Multiple capping agents

- Can control ratio of capping agent to crosslinker density - depending on final property requirements



**Note: Not to scale.*

PixJet & PixNIL High RI Formulations



- Curable liquid with capped nanocrystals + polymer/ monomer + additives
- Achieves a high level of performance:
 - ✓ *High RI*
 - ✓ *High level of reliability*
 - ✓ *Low shrinkage*
 - ✓ *Low dose UV curing – Air Curing*
 - ✓ *Smooth surface*
 - ✓ *Low particle defects*
 - ✓ *No pin hole*
 - ✓ *Clear light-path*
- Solvent-free or solvent-containing
- Compatible with commonly used deposition and manufacturing methods:
 - ✓ *Inkjet printing*
 - ✓ *Nano Imprint lithography*
 - ✓ *Inkjet/nanoimprint**
 - ✓ *Spin-coat*
 - ✓ *Dispense*
 - ✓ *Spray coating*
 - ✓ *Slot die coating*
 - ✓ *Screen printing*

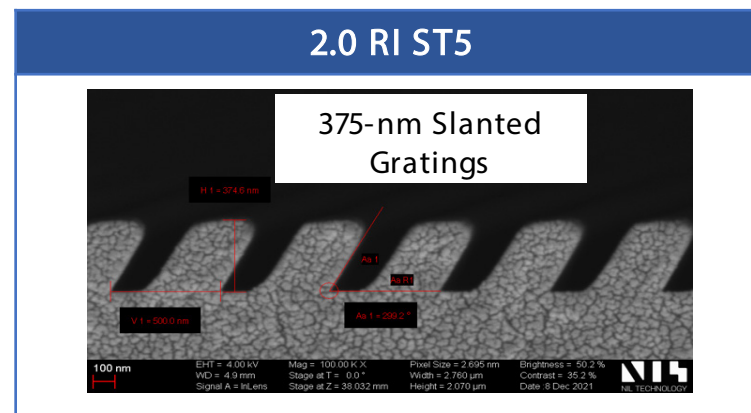
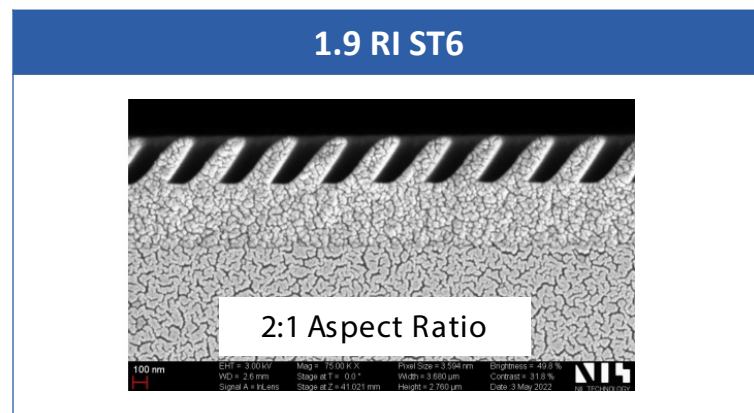
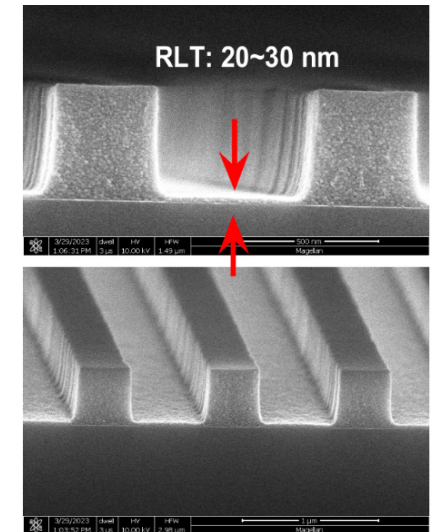


PixNIL® Solvent Containing Product Offerings



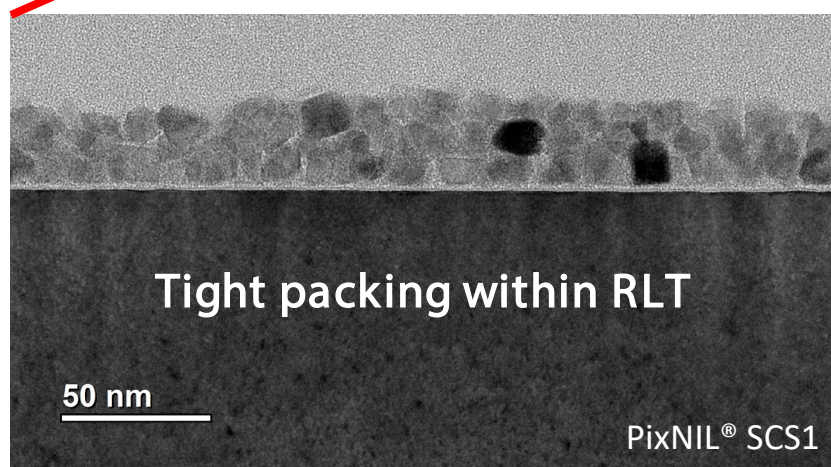
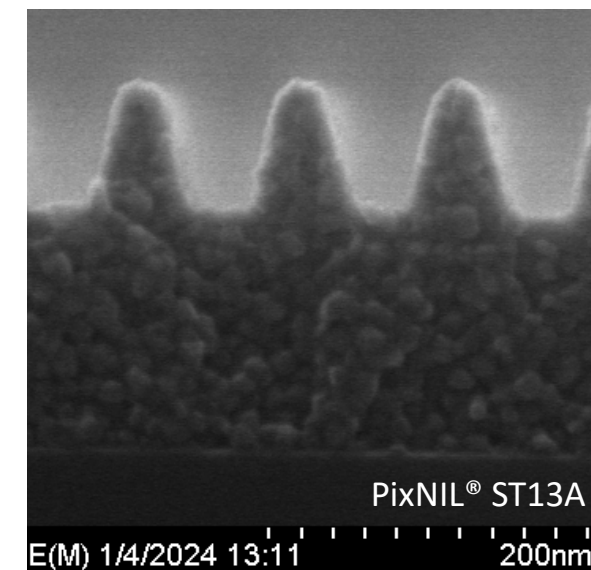
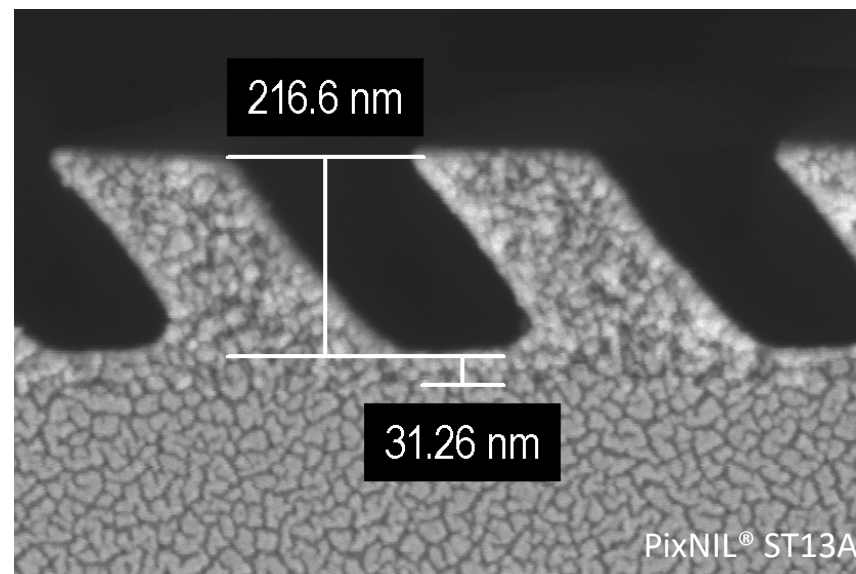
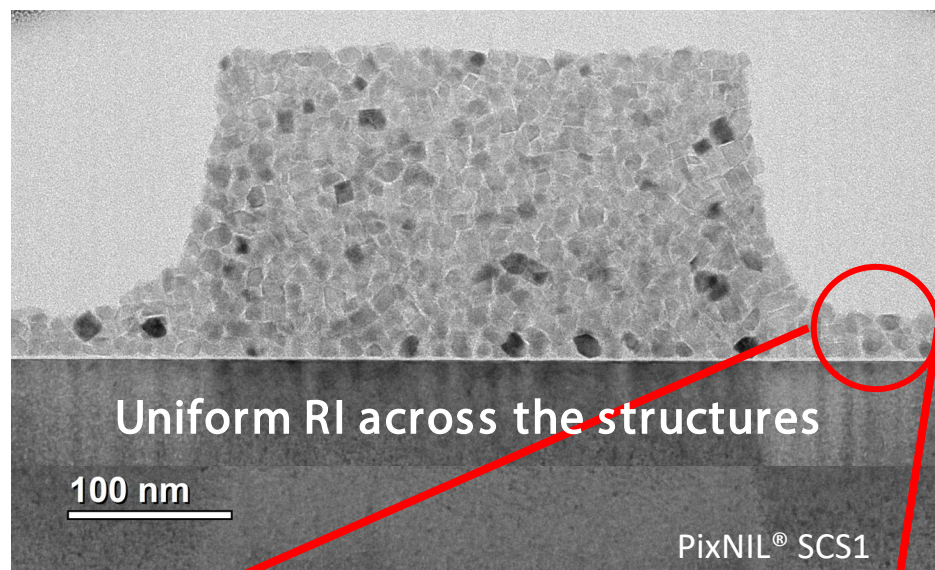
Product	Core	Solvent	Viscosity (cP)	RI (589 nm)
PixNIL® SZ1	Zirconia	Yes	4	1.7
PixNIL® SCS1	PixCor	Yes	4	1.86
PixNIL® ST13	Titania	Yes	4	1.86
PixNIL® ST2	Titania	Yes	4	1.9
PixNIL® ST5	Titania	Yes	4	1.98

✓ **PixNIL® ST2A** can achieve <50 nm Residual Layer Thicknesses

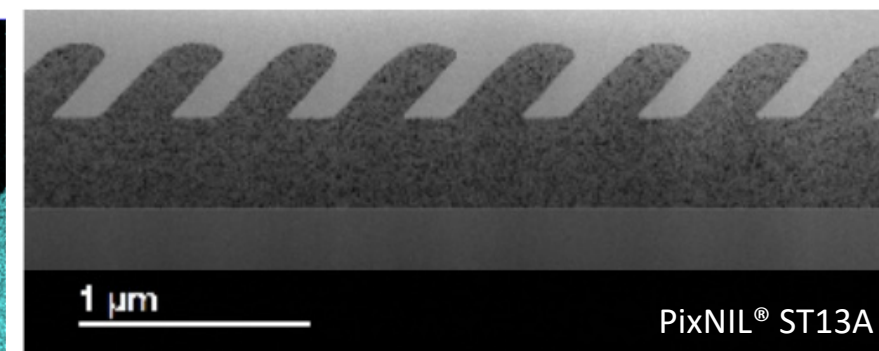
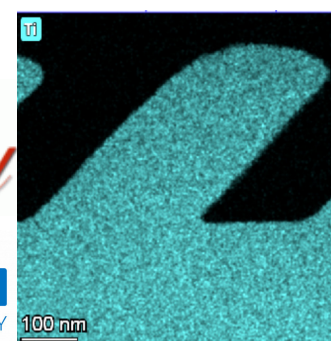


Courtesy of NIL Tech

Well-Distributed Nanoparticles in PixNIL® Nanoimprints



EVG 6200 NT SmartNIL UV NIL System



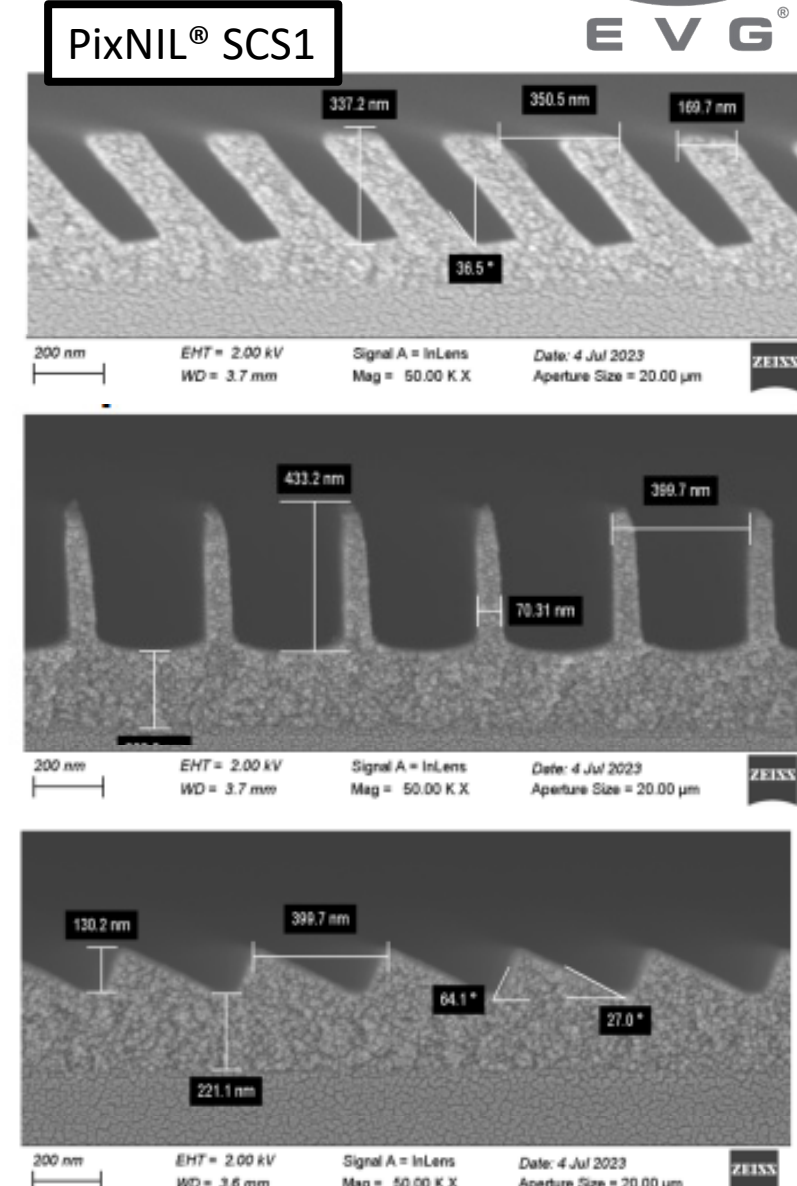
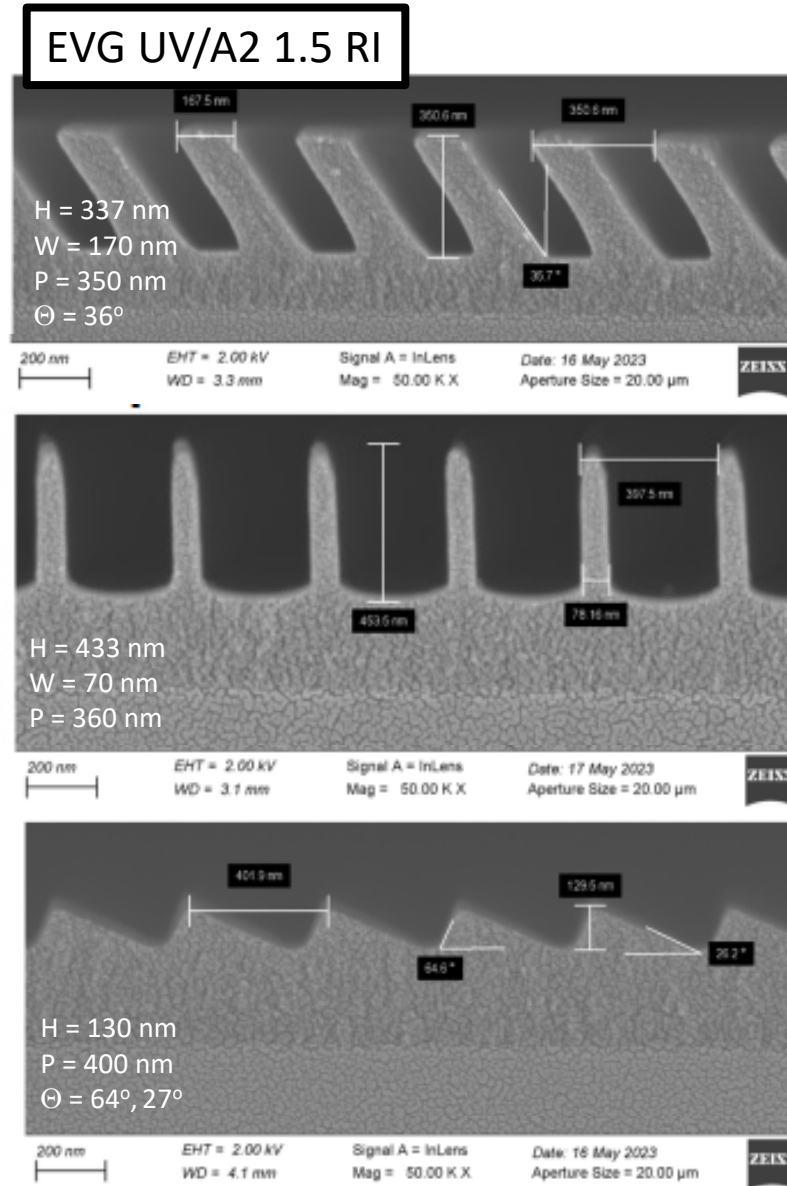
SMILE - Mask Aligner 8
Gen 5 - Imprint Tool



TEM images

Nanoimprinting

- Side-by-side comparison of EVG UV/A2 1.5RI imprint resin and PixNIL® SCS1
- Highlights:
 - Versatility of structures
 - Ability to fill small structures
 - Sharp edges (positive for NPs)
 - Use of AS5 (PFOS-free) stamp



Courtesy of EV Group

Improved Process Window

Spin Coat



Soft bake

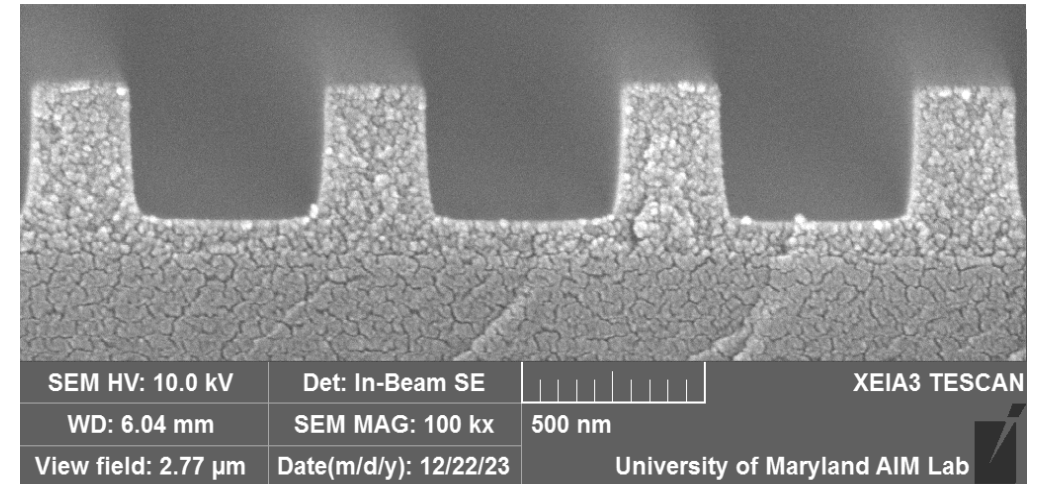


Imprint & UV cure

ST2A – Imprinting Process Window at 250 nm FT			
Temperature (°C)	Time (min)		
	1	2	3
50	Green	Green	Green
70	Green	Green	Green
80	Green	Red	Red
90	Red	Red	Red
100	Red	Red	Red

ST13A – Imprinting Process Window at 250 nm FT			
Temperature (°C)	Time (min)		
	1	2	3
50	Green	Green	Green
70	Green	Green	Green
80	Green	Green	Green
90	Green	Green	Green
100	Green	Red	Red

Imprinted with EVG A55 stamp: binary line grating structures with ~390 nm height
(green-pattern transfer success, red-pattern transfer failure)



ST13A imprinted at 250 nm film thickness after an 80° C/ 1min soft-bake; binary line grating structures with ~390 nm height.

Micro-Optics for 3D sensing and 3D Display Applications

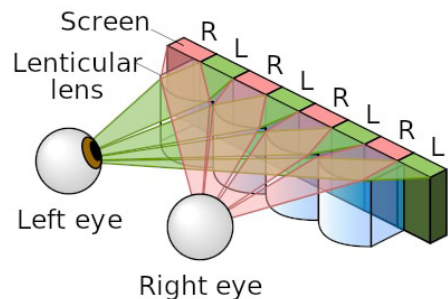
- ✓ HRI-based DOEs combine collimation and dot projection into a single component delivering advanced sensing performance in a compact form factor

- ✓ PixNIL® ST6: RI = 1.9, solvent-containing, >6:1 aspect ratio

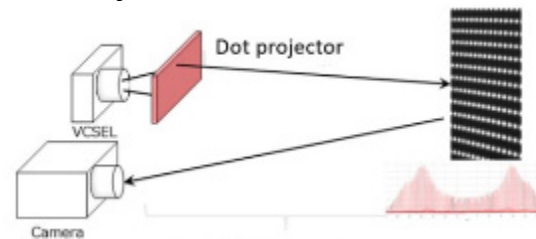
- ✓ HRI micron-scale lens structured diffusers enable improved **wide-angle sensing** for mobile phones and automotive interiors

- ✓ PixNIL® Solvent-free formulations, RI = 1.65-1.80, 30-50 µm films, MLA structure

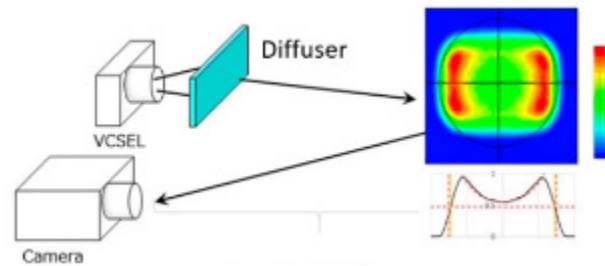
- ✓ Also used for 3D displays



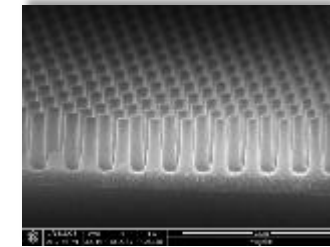
Dot Projector:



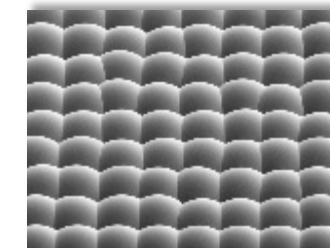
Diffuser:



PixNIL® high-index nano- and micro-imprinted components



Solvent-containing HRI resin (<1µm)



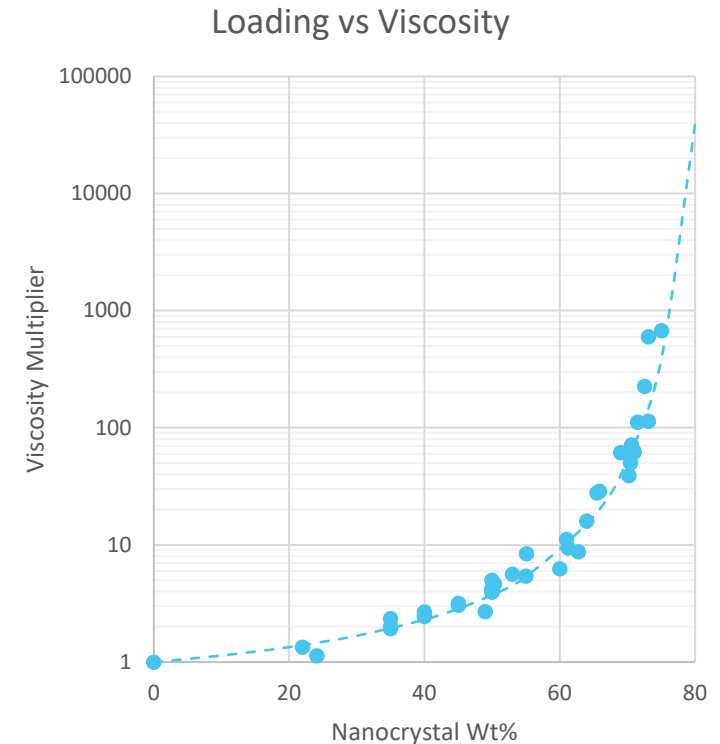
Solvent-free HRI resin (30-50µm)



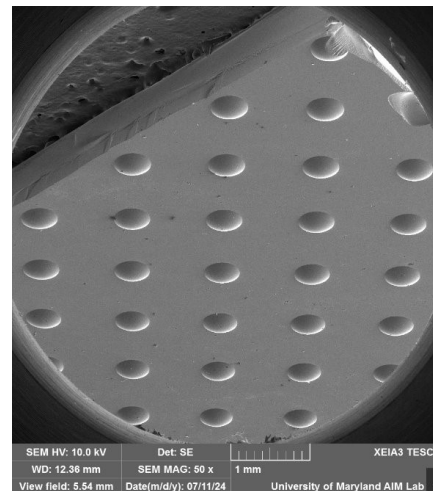
PixNIL[®] Solvent Free Product Offerings



Product	Core	Solvent	Viscosity (cP)	RI (589 nm)
PixNIL [®] SFZ4	Zirconia	No	550	1.65
PixNIL [®] SFZ1	Zirconia	No	850	1.70
PixNIL [®] SFCS1	PixCor	No	1500	1.80
PixNIL [®] SFT1	Titania	No	700	1.85
PixNIL [®] SFT2	Titania	No	1000	1.85



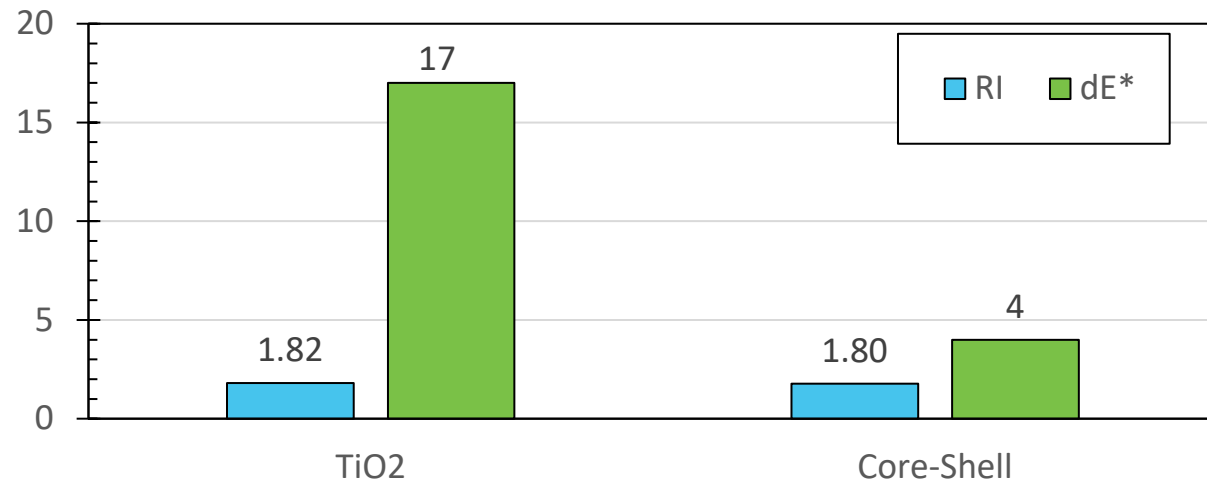
- Wafer Level Optics imprints shown
- Hemispherical lenses imprinted using Silicone stamp, Elastasil RT 601
- Compatible with PDMS stamps
- Looking for new applications and partners



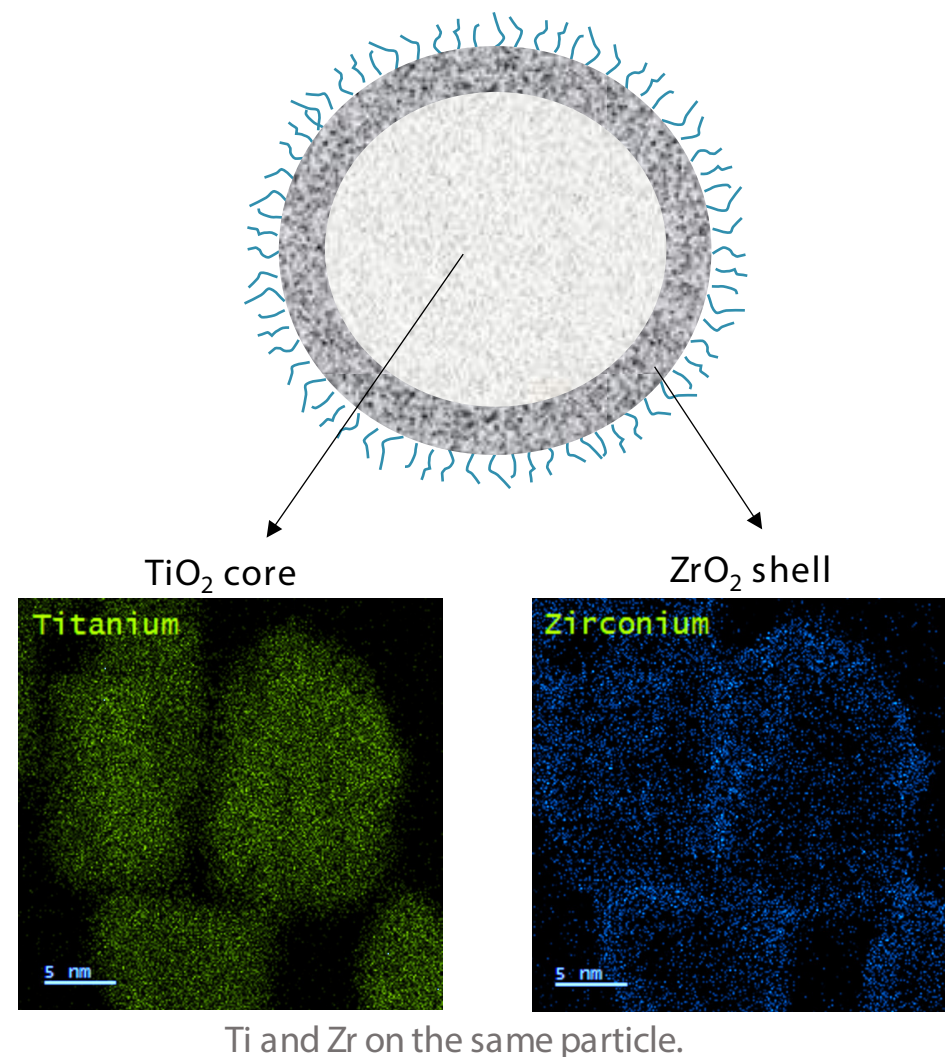
Award-Winning PixCor™ Formulations Improve TiO₂ Stability

PixCor™ TiO₂/ZrO₂ Nanocrystals

- 20-nm Core-Shell size by DLS with narrow particle size distribution maintained.
- Dispersions with no aggregation or settling.
- Compatible with various solvents/ monomers.
- > 85% improvement in light stability with 405 – 450 nm exposure.
- Same compatibility as PixNIL® formulations in similar resin systems.
- Films with > 95% transmission, < 0.1% haze.



Q-Sun (AM1.5, 400nm filter, 500 hrs.), 20 μm FT



The PixClear®, PixNIL® & PixJet® Advantage



Market Leading Properties:

- ✓ HRI 1.7 – 2.0+
- ✓ 95%+ Transparency
- ✓ <0.1% haze
- ✓ Loadings up to 80%
- ✓ Uniform Dispersions

Varied Processing Conditions:

- ✓ Solvent-Free
- ✓ Solvent-Containing
- ✓ Nanoimprintable
- ✓ Spin-Coating
- ✓ Inkjet Printing & Jet Coating
- ✓ Bake / No Bake

Formulations are tunable to suit application needs:

- ✓ Viscosity
- ✓ Film RI
- ✓ Film thickness & NIL residual layer thickness
- ✓ Optimal RI to RLT Ratios
- ✓ Reliability/ Absorption Requirements
- ✓ Drop-in Ready



Tunable Properties

Thank You

Questions?





Contact Us

Email: marketing@pixelligent.com

Web: www.pixelligent.com

Phone: 443.529.8310

Address: 6411 Beckley Street Baltimore, MD 21224



<https://www.linkedin.com/company/pixelligent-technologies-llc/>



<https://twitter.com/Pixelligent>